

Title (en)

PHOTORESIST REMOVER COMPOSITIONS

Title (de)

PHOTOLACKENTFERNERZUSAMMENSETZUNGEN

Title (fr)

COMPOSITIONS DE DÉCAPAGE DE RÉSINE PHOTOSENSIBLE

Publication

EP 3997521 B1 20230830 (EN)

Application

EP 20740561 A 20200709

Priority

- US 201962872950 P 20190711
- EP 2020069326 W 20200709

Abstract (en)

[origin: WO2021005140A1] The present invention relates to a composition including a sulfonic acid selected from the group consisting of an alkylbenzenesulfonic acid having structure (I), or its hydrate (wherein n is an integer from 6 to 16), a sulfosalicylic acid having structure (II), or its hydrate, and mixtures thereof and the solvent dipropylene glycol dimethyl ether [CAS registry number 111109-77-4] (III);

IPC 8 full level

G03F 7/42 (2006.01)

CPC (source: CN EP KR US)

B08B 3/08 (2013.01 - US); **B08B 3/10** (2013.01 - US); **G03F 7/426** (2013.01 - CN EP KR US); **B08B 2203/007** (2013.01 - US)

Designated contracting state (EPC)

AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

DOCDB simple family (publication)

WO 2021005140 A1 20210114; CN 114080571 A 20220222; EP 3997521 A1 20220518; EP 3997521 B1 20230830; JP 2022540087 A 20220914; JP 7389886 B2 20231130; KR 102609919 B1 20231204; KR 20220034813 A 20220318; TW 202111448 A 20210316; TW I824164 B 20231201; US 11994803 B2 20240528; US 2022276562 A1 20220901

DOCDB simple family (application)

EP 2020069326 W 20200709; CN 202080050038 A 20200709; EP 20740561 A 20200709; JP 2022500553 A 20200709; KR 20227003643 A 20200709; TW 109123194 A 20200709; US 202017596852 A 20200709